

## Electronic Supplementary Information

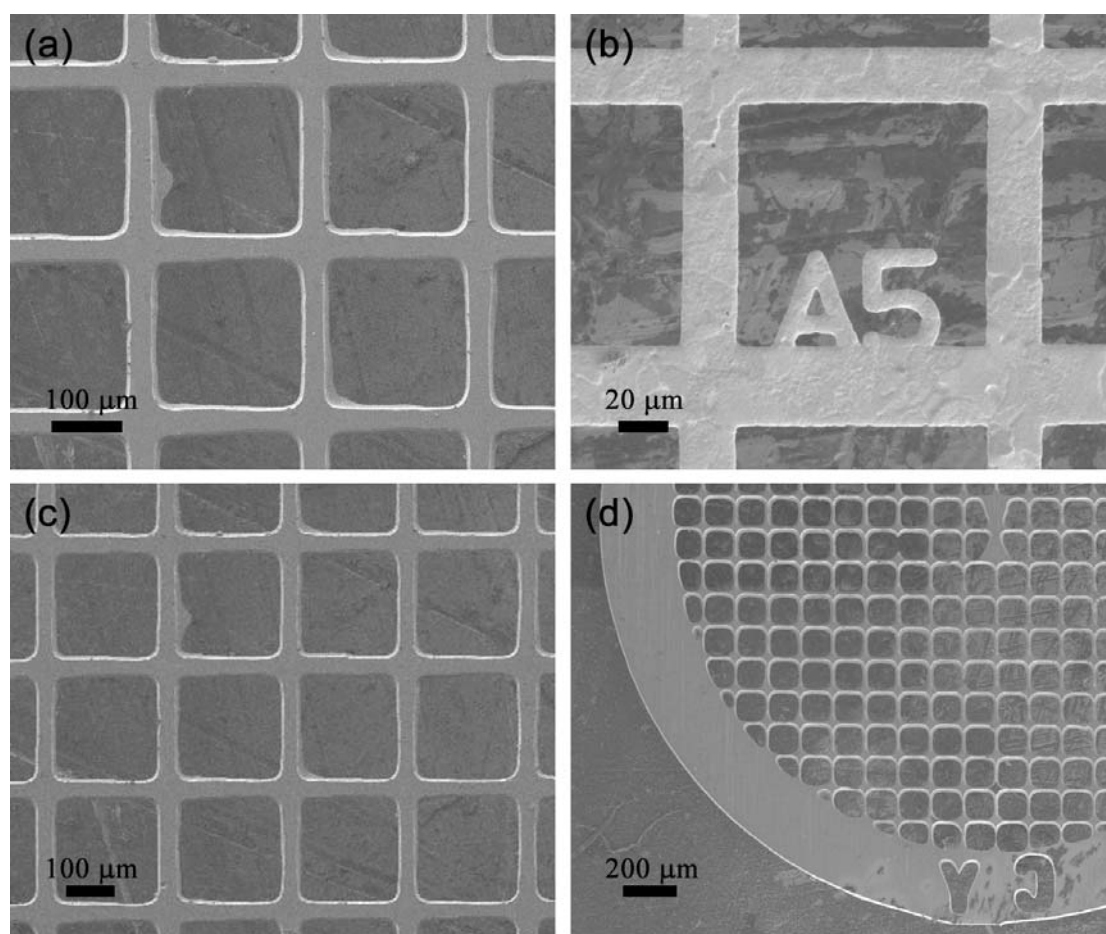
### **Patterning of hydrophobic three-dimensional carbon nanotube architectures by a pattern transfer approach**

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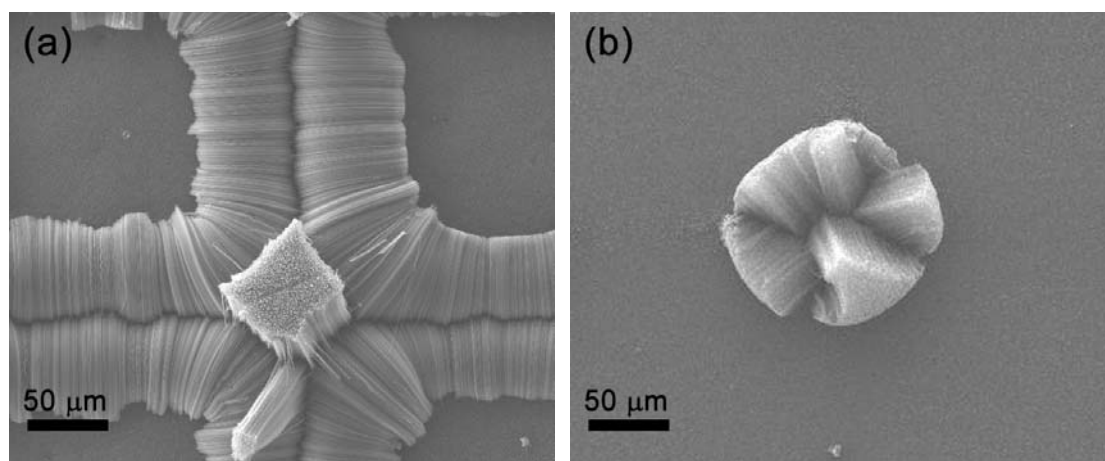
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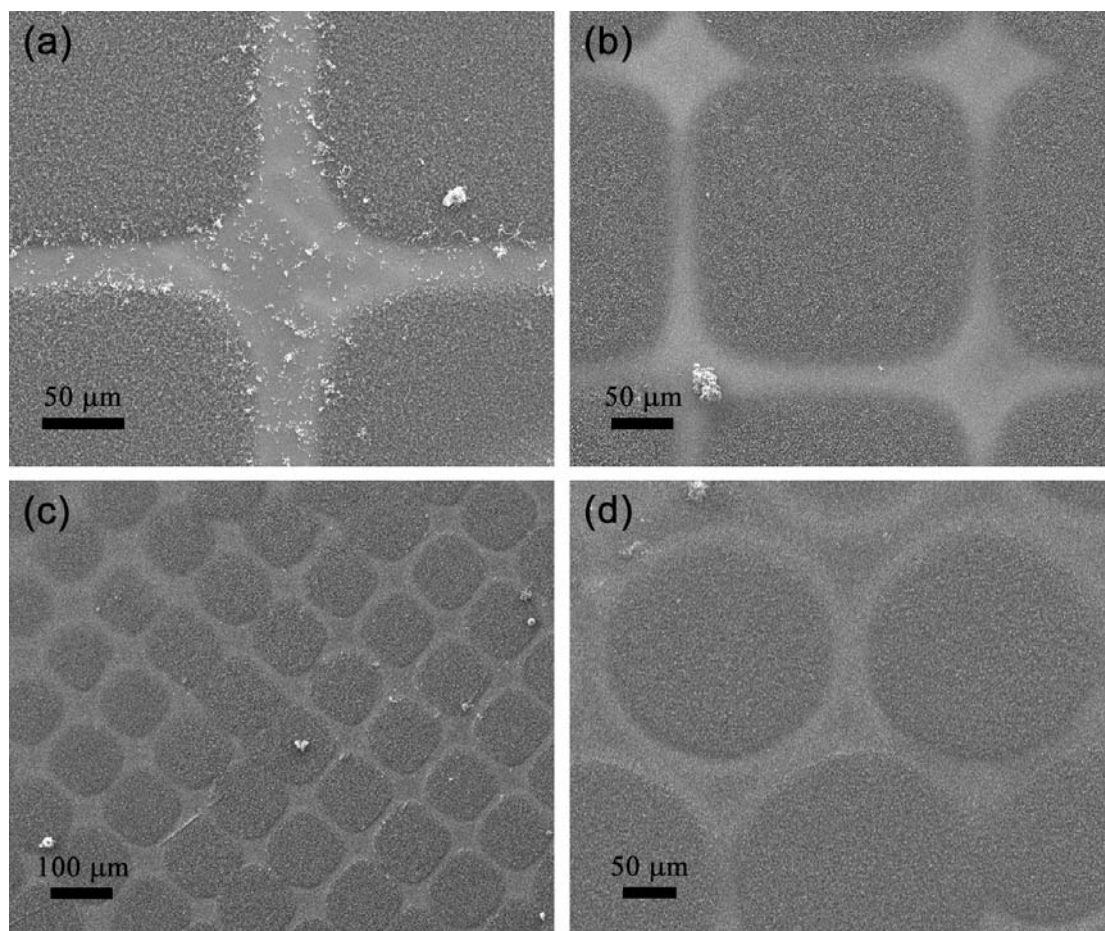
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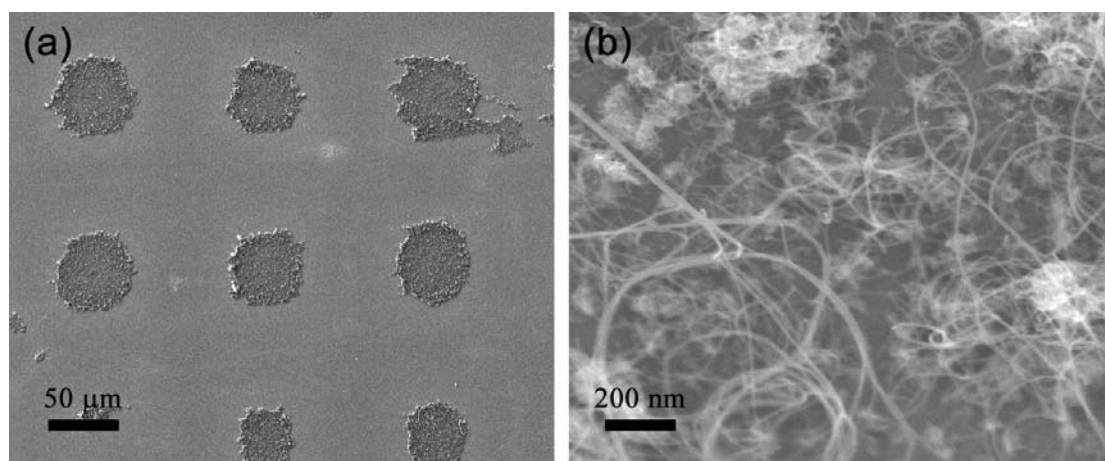
**Fig. S1** The SEM images of micro grid masks corresponded to the obtained CNT architectures in Fig. 1a, 1b and Fig. 3a, 3b.



**Fig. S2** (a) The enlarged image of Fig. 1a and (b) the enlarged image of Fig. 3a, showing the detailed morphology of the multi-directional growth of CNT arrays.



**Fig. S3** The results of the CNT growth under different masks: (a) Cu grid; (b) Fe grid; (c) W grid; (d) Ni grid. The growth of CNTs in the covered area was limited.



**Fig. S4** (a) the SEM image of the silicon substrate after the removal of CNT architectures in Fig. 2d. The black dots in the image referred to the uncovered area; (b) the enlarged SEM image of the uncovered area, showing the formation of a sparse CNT film.